

Listing of Claims

Please amend the claims as follows. The following list of claims will replace all prior versions and listings of claims in the application.

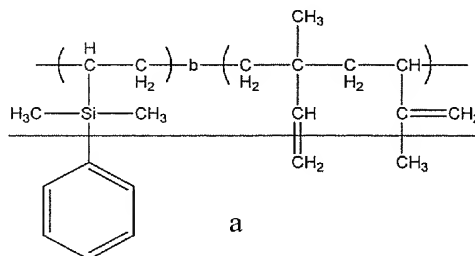
1–11. (Canceled)

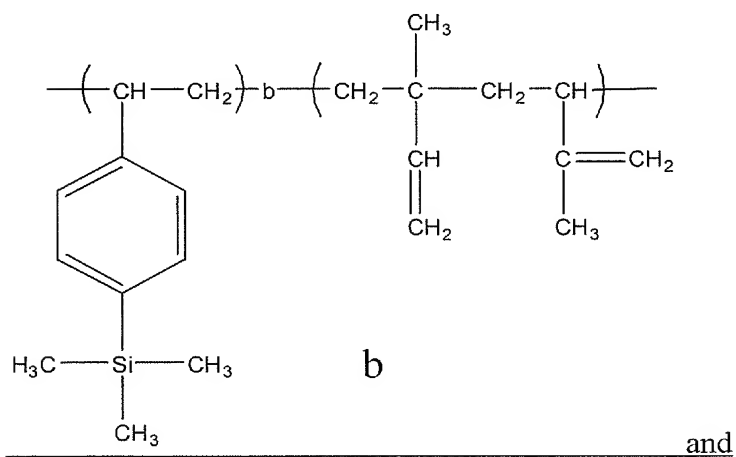
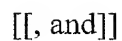
12. (Previously Presented) A resist composition, comprising a silicon-containing resist polymer, wherein the silicon-containing resist polymer comprises poly(dimethylphenylvinylsilane-b-isoprene) having a molecular weight between about 17,800 and about 22,100.

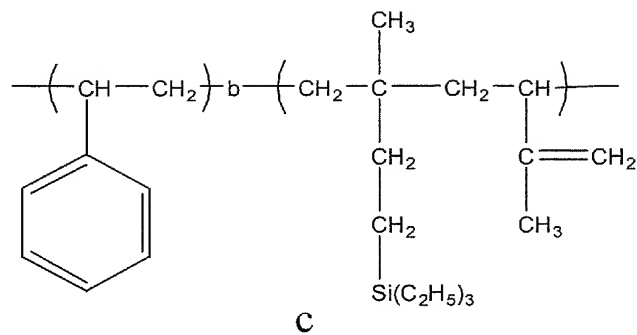
13. (Previously Presented) A resist composition, comprising a silicon-containing resist polymer, wherein the silicon-containing resist polymer comprises poly(trimethylsilylstyrene-b-isoprene) having a molecular weight between about 10,700 and about 28,700.

14–18. (Canceled)

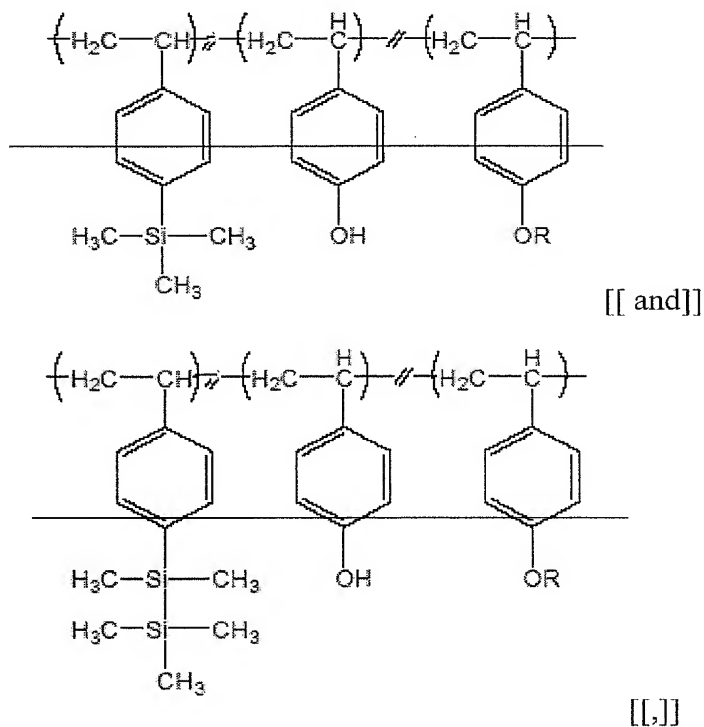
19. (Currently Amended) A resist composition, comprising a silicon-containing resist polymer, wherein at least a portion of the silicon-containing resist polymer comprises a structure selected from the group consisting of:

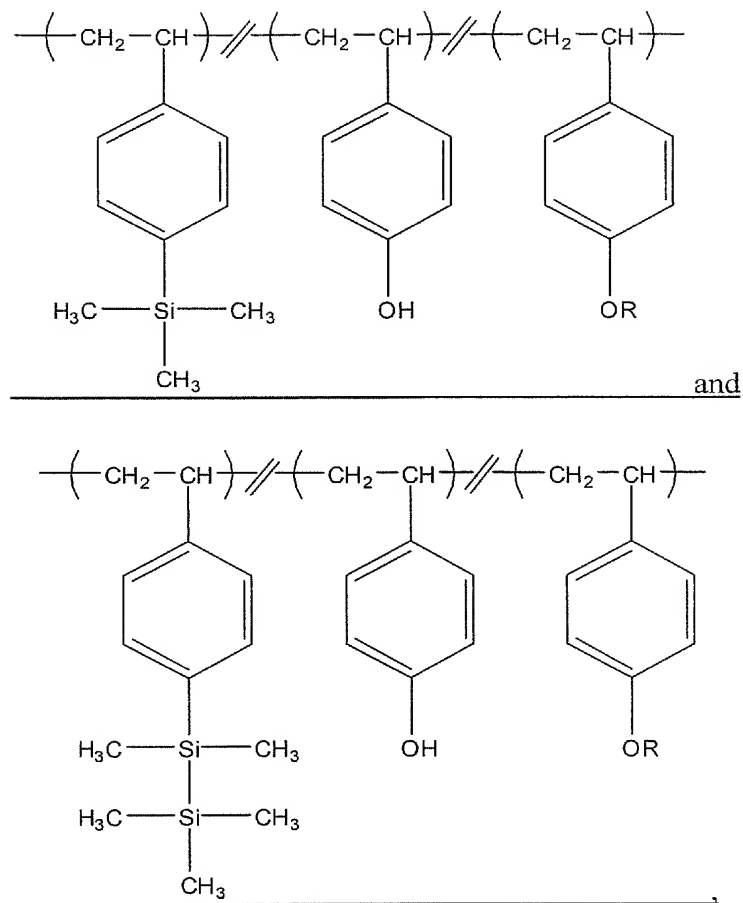






20. (Currently Amended) A resist composition, comprising a silicon-containing resist polymer, wherein at least a portion of the silicon-containing resist polymer comprises a structure selected from the group consisting of





wherein R represents a protecting group.

21. (Original) The resist composition of claim 20, wherein the protecting group R is selected from the group consisting of t-butyloxycarbonyl, trimethyl silane, and ethoxymethyl.

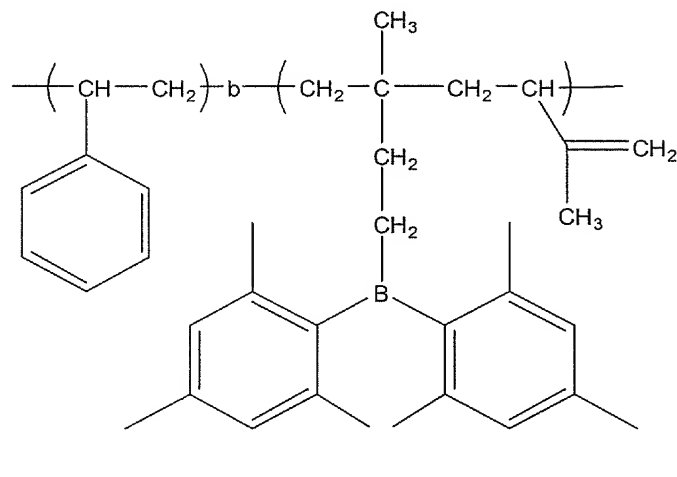
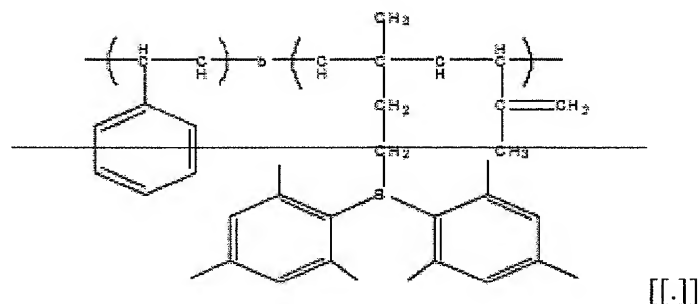
22–25. (Canceled)

26. (Previously Presented) A resist composition, comprising a boron-containing resist polymer,

wherein the boron-containing resist polymer comprises less than about 1 weight percent boron, and further comprises an element selected from the group consisting of carborane carboxylic acid, dimesitylborane and combinations thereof.

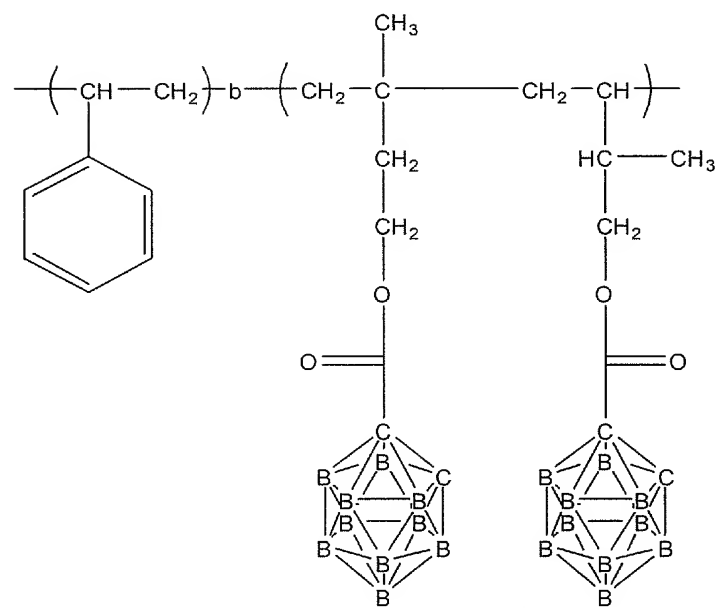
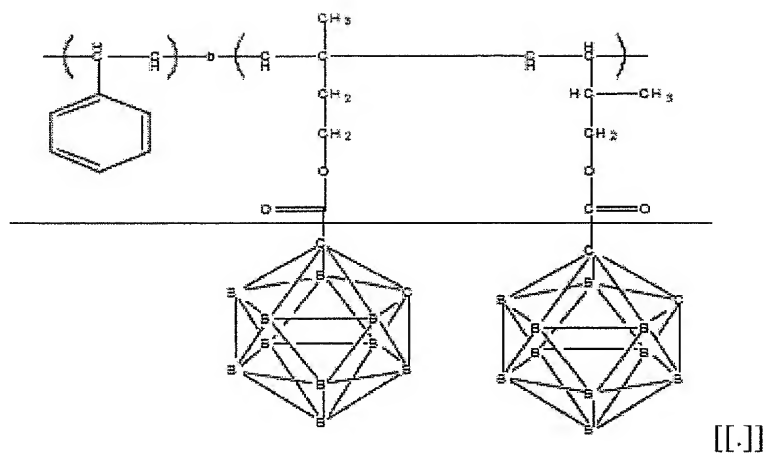
27-31. (Canceled)

32. (Currently Amended) A resist composition, comprising a boron-containing polymer, wherein the boron-containing polymer comprises a polymer having the structure:

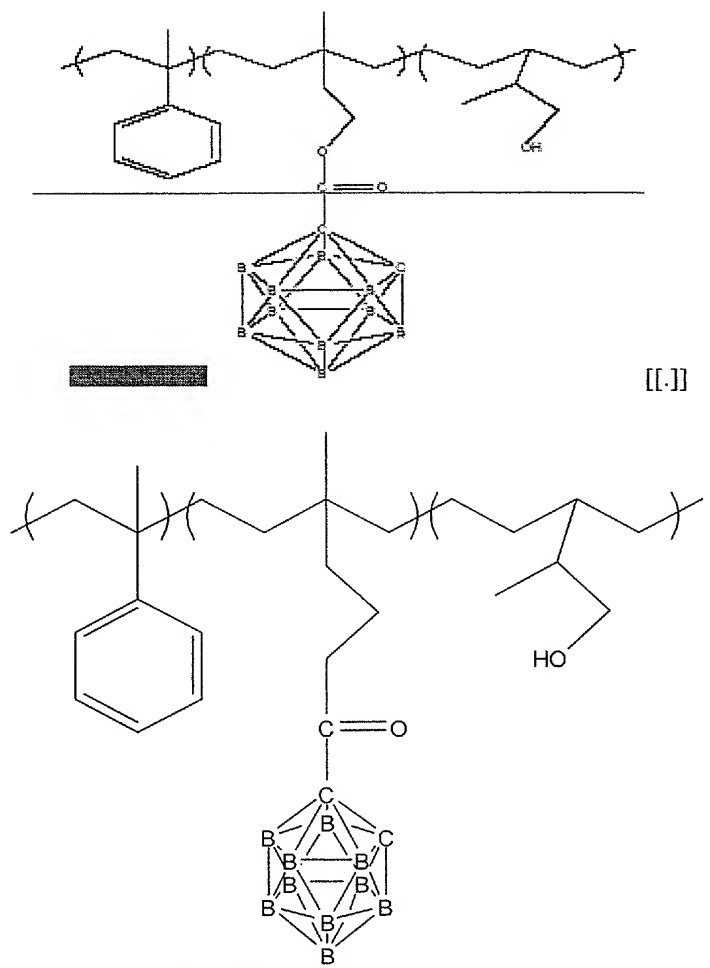


33. (Original) The resist composition of claim 32, wherein the resist composition comprises less than about 1 weight percent boron.

34. (Currently Amended) A resist composition, comprising a boron-containing polymer, wherein the boron-containing polymer comprises a polymer having the structure:



35. (Currently Amended) A resist composition, comprising a boron-containing polymer, wherein the boron-containing polymer comprises a boron-containing polymer having the structure:



36-47. (Canceled)

48. (Previously Presented) A method for forming a boron-containing resist polymer, comprising performing a hydroboration or esterification reaction of a boron-containing group with a polymer, wherein the polymer comprises a polymer selected from the group consisting of poly(styrene-b-isoprene) and hydroxylated poly(styrene-b-isoprene), to introduce dimesitylborane or a carborane into the polymer.

49-66. (Canceled)